Q. Metrology, Inspection, and Yield Enhancement 분과

Room F
봉래 I (6층)

2016년 2월 24일(수) 08:30-10:00
[WF1-Q] Metrology and Inspection Ⅱ
좌장 : 김재현(SK 하이닉스), 김진승(전북대학교)

WF1-Q-1 **08:30-08:45** **Guide Line of Optimizing Wafer Position Map of High Order Overlay Models**
Seung Hyun Jeong
Department of NM Process Photo Team Research and Development Division, SK hynix Inc.

WF1-Q-2 **08:45-09:00** **Development of A Field Emission Nano-Focus X-ray Source with Electrostatic and Magnetic Lenses for Semiconductor Inspections**
Yoon-Ho Song[1,2], Sora Park[1], Jae-Woo Kim[1], Jun-Tae Kang[1], Jin-Woo Jeong[1], Ji-Hwan Yeon[1], Min-Sik Shin[1,2], Sunghee Kim[1], Eunsol Go[1,2], Hyojin Jeon[1,2], and Young Chul Choi[1]
[1]Nano Electron-Source Creative Research Center, Electronics and Telecommunications Research Institute, [2]School of Advanced Device Engineering, University of Science and Technology

WF1-Q-3 **09:00-09:15** **Deep Learning을 이용한 TSOM 이미지 계측**
Heechul Choi, Hyeongbok Kim, and Joonghwee Cho
Department of Embedded Systems Engineering, Incheon National University

WF1-Q-4 **09:15-09:30** **Individual Multiwall Carbon Nanotube Field Emitter As Electron Source for Scanning Electron Microscope**
Sanjeev Kumar Kanth[1,2], Anjli Sharma[2], Byong Chon Park[1], and Ho Seob Kim[2]
[1]Center for Nanometrology, Korea Research Institute of Standards and Science, [2]Department of Nanoscience, Sun Moon University

WF1-Q-5 **09:30-09:45** **A Methodology for Test Macro Generation based on Classification of Unique Patterns**
[1]MinSoo Kang, [1]Jong-hyun Lee, [1]Chin Kim, [2]Mohammed Harb, and [1]Sun-Hom Steve Paak
[1]Samsung Electronics Co., Ltd., [2]Mentor Graphics Corporation, Egypt

WF1-Q-6 **09:45-10:00** **Image Processing 기술을 활용한 불량 검출력 향상 연구**
Kyu-Young Kim, Sungjin Kwon, Seong-Min Ma, Deok-In Kim, and Kyu-Chan Shim
SK hynix Inc.